Development Status of a CVD System to Deposit Tungsten onto UO_2 Powder via the WCl₆ Process

NASA Advanced Exploration System (AES) Project: Nuclear Cryogenic Propulsion Stage

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Background

NTP fuels under development

- W-60vol%UO₂ CERMET
 Fuel loss through erosion
- Inherently stable W fuel element cladding
- Coat spherical UO₅ fuel kernels in 40 vol% W



331 and 7 channel fuel samples

- Performance Advantages
 - Prevent H₂ propellant at 2850 K from reducing UO₂ fuel kernels
 - Minimize erosion and fuel loss

Manufacture Advantages

- Excellent powder distribution uniformity during HIP can fill
- Prevents segregation during HIP can fill
- Higher green packing density
- Minimize dimensional distortion during HIP

Problem & Objectives

- Vendor cost to coat duo, in W excessive
- WF₆ process
 - Industry standard for W deposition
 - Gaseous reagent
 - Excessive F contamination in UO₂ substrate and W coating
 - Residual F exacerbates fuel loss

WCl₆ process

- No UO_2 chlorination with WCI_6 or reaction products
- W coatings do not excessively contaminate substrate
- WCl₆ preferable to WF₆ for coating UO₂ with W
- More complex (solid-to-vapor reagent gas)
- Not an industrially utilized process
- Develop a lab-scale prototype that utilizes the WCl₆ process that enables cost effective 40vol% coating of spherical dUO₂ powders



SEM micrograph of uncoated UO₂ sol-gel particles (700x)



SEM micrographs of spherical W-coated ZrO₂ particles

Coating Requirements

- Fully encapsulate UO₂ substrate
- Thickness: 40 ± 1 vol%, uniform spatial distribution
- Density: pore-free, 18.7 g/cm³ 19.2 g/cm³
- Purity: > 99.98% W, \leq 10 ppm impurities
- Process: must not react with UO₂ substrate
- Adhesion: must not de-bond, spall, crack or blister up to 3000 K
- UO₂ fuel loss: <1.9 wt% (<1 mg/cm²) when heated to 3000 K in flowing H₂ for 2 hours

Apparatus

WCl₆ process

- Temperature: 950°C (higher results in large columnar grains
- H₂/WCl₆ mole ratio: 10:1 to 30:1
- Pressure: < 10 mm Hg (0.193 psia)
- CVD System
 - Fluidized bed reactor
 - Raining feed, 25 g batches
 - 20 to 60 min

 $WCl_6 + 3H_2 \xrightarrow{Ar, xs H_2, 930^{\circ}C} W + 6HCl + Ar + xs H_2$





Spouted Reactor

Accomplishments

- Fluidization of ZrO₂
- Coating ZrO₂ to 60% of target thickness in 20 minutes
- Demonstrated viability of the WCl₆ CVD process
- Coating spatial uniformity (thickness measured through cross section examination)
- Path: ZrO_2 , HfO_2 , UO_2

Limitations

- Powder drop-out. difficult to fluidize HfO₂ without high H₂ flow rates & powder small quantities
- Complex design
- Fragile and expensive glassmetal transition



Spouted reactor design. Fluidization pre & post deposition process







ZrO₂, $D_{p,u}$ = 14.519 μm, 20 min run, t = 2.1184 μm (157.2% of goal) Deposition rate = 6.3552 μm/hr.

Fluidization

Calculate fluidization conditions

 Estimate Reynolds number and terminal velocity of powders in a fluidized state.

Empirical data

- Develop correlations based on empirical data
- Verify correlations with observed fluidization behavior

Reactor estimation

- Extrapolate calculated and empirical results to estimate minimum fluidization flow rate
- Reactor design and particle specific

Powder	Theoretical Density (g/cm³)	Actual Density (%TD)	Particle Size (µm)
ZrO ₂	5.68	50	53 - 106
HfO_2	9.68	99	100 – 200
	10.97	99	50 – 150

$$Re_{mf} = (29.5^2 + 0.375Ar)^{1/2} - 29.5$$

$$Ar = \frac{gD_p^3\rho_f(\rho_p - \rho_f)}{\mu_f^2}$$

$$V_T = \frac{2gD_p^2(\rho_p - \rho_f)}{18\mu_f}$$

- Re_{mf} = Reynolds number for minimum fluidization (sphereicity > 0.93)
- Ar = Archimedes number
- g = gravity
- D_p = particle diameter
- ρ_p = particle density
- ρ_f = fluid density
- μ_f = fluid viscosity
- \vec{V}_T = particle terminal velocity

Inverted Reactor

Fluidization Prototype

- Simplified & robust design
- Based on lessons learned
- Co-centric fluid lines
- Built and tested

Fluidization

- HfO₂ (30, 60, 100, 200 g)
- Room temperature argon
- Fluidization vs. flow rate
- Inner/outer fluidization line
- Straight vs. tapered reactor wall
- Fluidized column height behavior
- Determined minimum and optimum fluidization flow rates
- Data used to design inverted CVD reactor



Co-centric tube positions

Fluidization: Tapered, 103 g HfO₂, Ar, 30 L/m outer, 1 L/m inner, flush.



Powder loading and fluidization vs powder mass

Inverted Reactor Geometry

Reactor manifold

- Pyrex
- Co-centric reactant and fluidization lines
- Ball-socket gas connections

Reactor Wall

- Quartz
- Tapered
- Contains powder, eliminates powder drop out collection hopper

Reactor O-ring Joint

- Standard item
- Eliminates glass-to-metal transitions
- Thicker walls = robust
- Inverted Reactor
 - UO₂ fluidization and coating trials in March



Additional CVD Upgrades



Inverted Reactor System Layout



Gas line simplification, fitting/valve reduction

Inverted reactor sublimer



Data Acquisition and Control System



Reactor handling glove box.



Kalrez 4079 O-rings

Conclusions

 Demonstrated viability of the WCl₆ CVD process to coat ZrO₂ particles with W.

- Inverted reactor designs are far more forgiving and robust than spouted designs.
- Corrosive nature of WCl₆ vapor limits reactor material to Inconel, pyrex, quartz.
- Transition from surrogate to dUO₂ powder as quickly as possible in order to address changes in process variables specific to dUO₂.

Recommendations for Future Work

Optimize process variables WCl₆ powder, H₂, Ar impurity content Reactor temperature

- Reactor heat/cool rates
- H₂/WCl₆ mole ratio
 Flow rates as a function of coating thickness
- Deposition rate as a function of particle size

Coating characterization

- Thickness
- Spatial uniformity
- Impurity content
- Adhesion
- Micro-hardness
- Surface roughness
- Grain structure (epitaxial content, grain orientation)
- Grain orientation effect on coating properties (heat transfer/diffusion)
- Grain boundary population impact on fuel retention

Potential H_2 heat treatments

- Pre-deposition to clean substrate surface: effect on coating adhesion
 Post-deposition to remove impurities: effect on W grain growth

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